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Dielectric and Raman spectroscopy of TISe thin films

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**Abstract** 

In this report, the results of Dielectric and Raman spectroscopy of TISe thin films are

presented. The films were deposited in different thicknesses ranging from 290Å to 3200Å

by thermal evaporation method. The relative permittivity (dielectric constant  $\varepsilon_r$ ) and

dielectric loss (E<sub>r</sub>") of TlSe thin films were calculated by measuring capacitance (C) and

dielectric loss factor (tan  $\delta$ ) in the frequencies ranging between  $10^{-2}$  Hz to  $10^{7}$  Hz and in the

temperature ranging between 173 K to 433K. In the given intervals, both the dielectric

constant and the dielectric loss of TISe thin films decrease with increasing frequency, but

increase with increasing temperature. This behavior can be explained as multicomponent

polarization in the structure. The ac conductivity obeys the  $\omega^s$  law when s(s<1). The

dielectric constant of TISe thin films is determined from Dielectric and Raman spectroscopy

measurements. The results obtained by two different methods are in agreement with each

other.

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